



Patent  
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

4/6/01  
#9  
D)

Re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT

Group Art Unit: 1756

Examiner: S. Mohamedulla

**PETITION FOR EXTENSION OF TIME**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

The following extension of time is requested to respond to Office Action dated December 5, 2000 and Advisory Action dated March 14, 2001:

one month to April 5, 2001; the extension fee is:

☐ \$55.00 (215) ☒ \$110.00 (115).

☐ The shortened statutory period has been reset by an Advisory Action dated

☒ An extension fee in the amount of \$ 110.00 is enclosed.

☐ Charge \$ \_\_\_\_\_ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By:

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Registration No. 32,131

04/05/2001 JADD01 00000008 09320946  
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Date: April 4, 2001

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